

[Abstract]

The present invention addresses the problem of providing a decomposition inhibitor for inhibiting the decomposition of hydrogen peroxide included in an etching liquid composition for titanium nitride.

The present invention relates to a decomposition inhibitor that is used to inhibit the decomposition of hydrogen peroxide included in an etching liquid composition for titanium nitride and that includes at least one compound selected from amongazole compounds, aminocarboxylic acid compounds, and phosphonic acid compounds as an active component.

FIG. 1 accompanies abstract